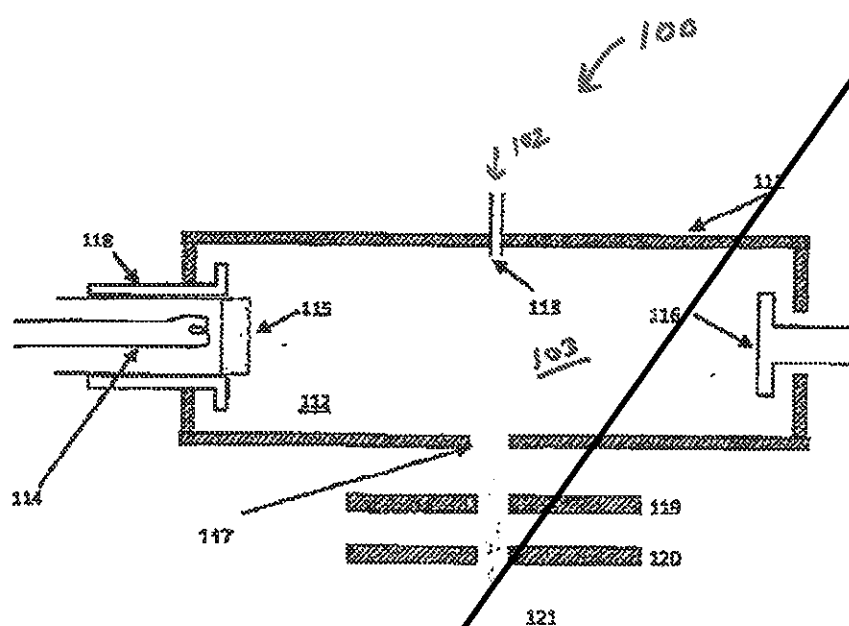


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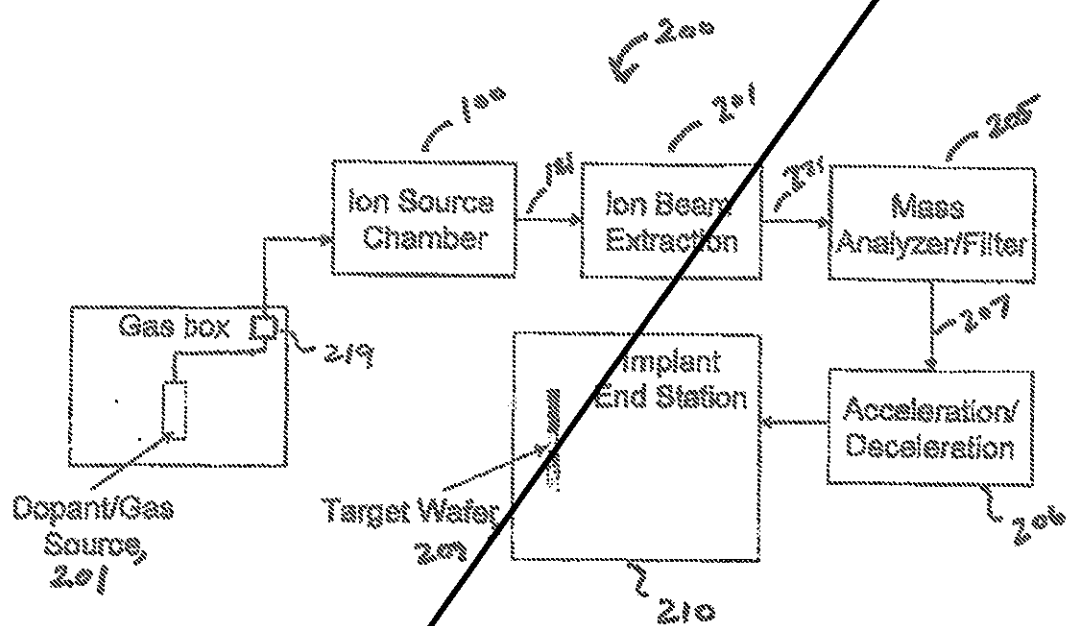


Schematic of an ion source apparatus

FIG. 1

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FIG. 2



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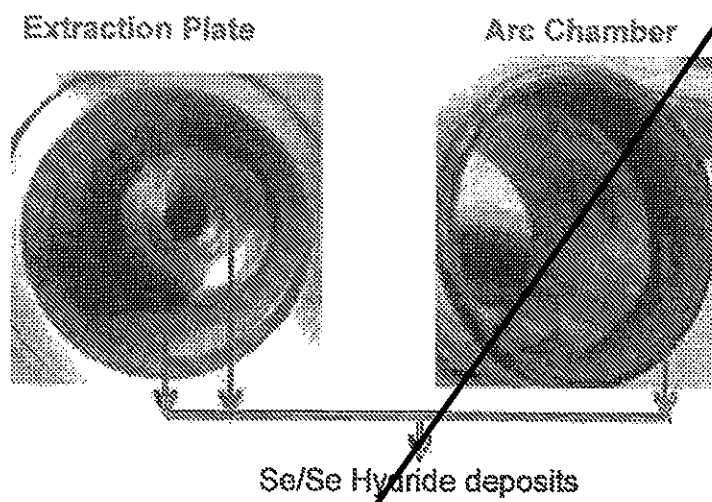


Figure 3a and 3b: Deposits during H_2Se Implant

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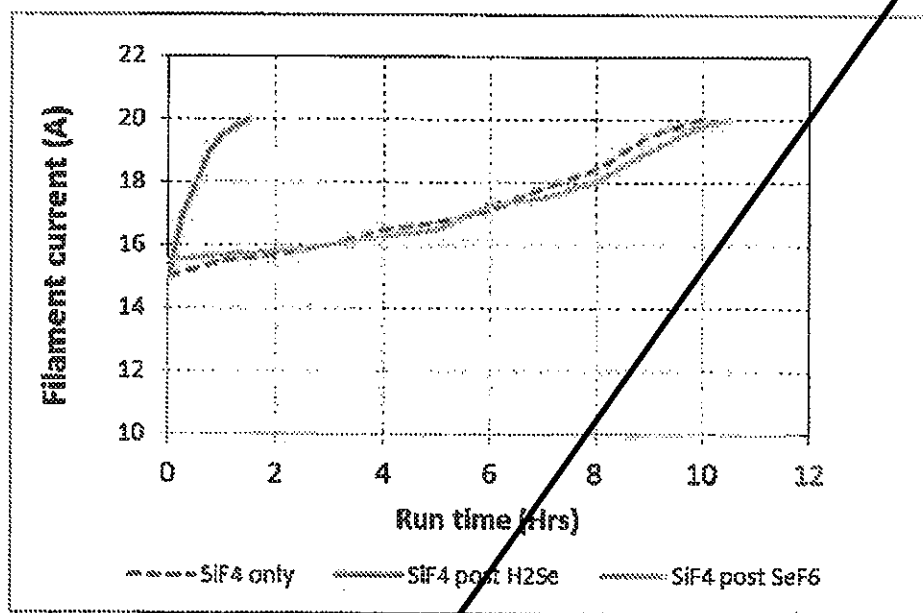
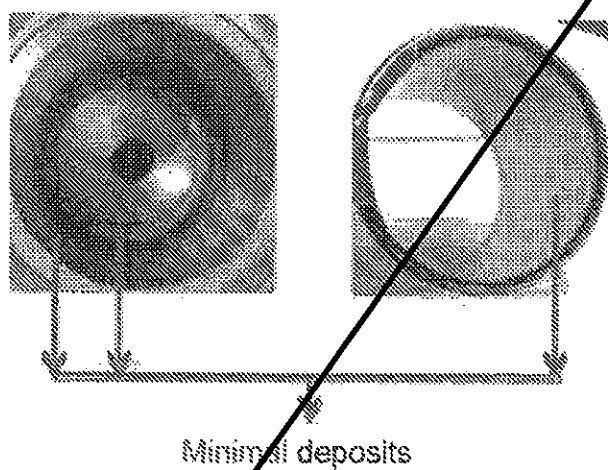
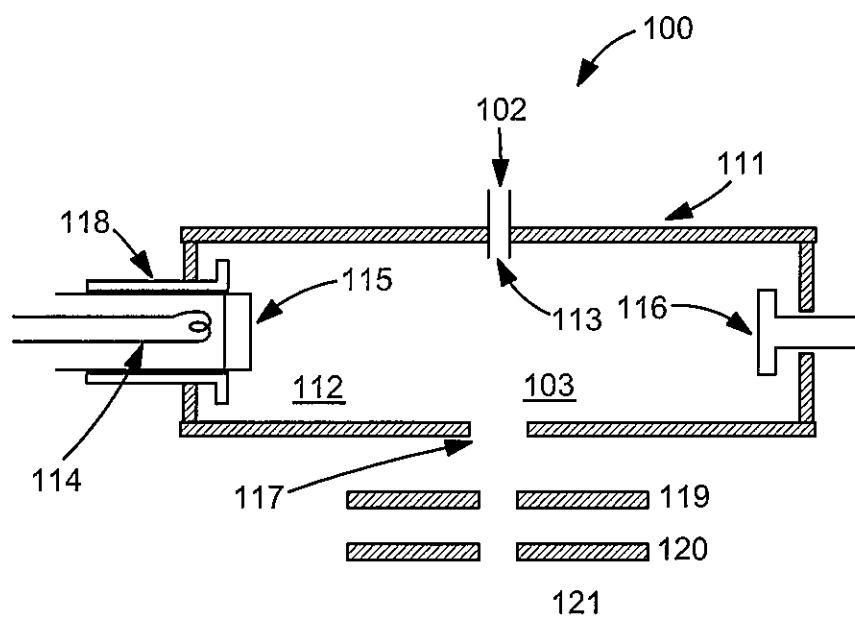


Figure 4: Filament current trend during SiF4 implant

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Figures 5a and 5b: Deposits during enriched SeF_6 Implant





Schematic of an ion source apparatus

FIG. 1

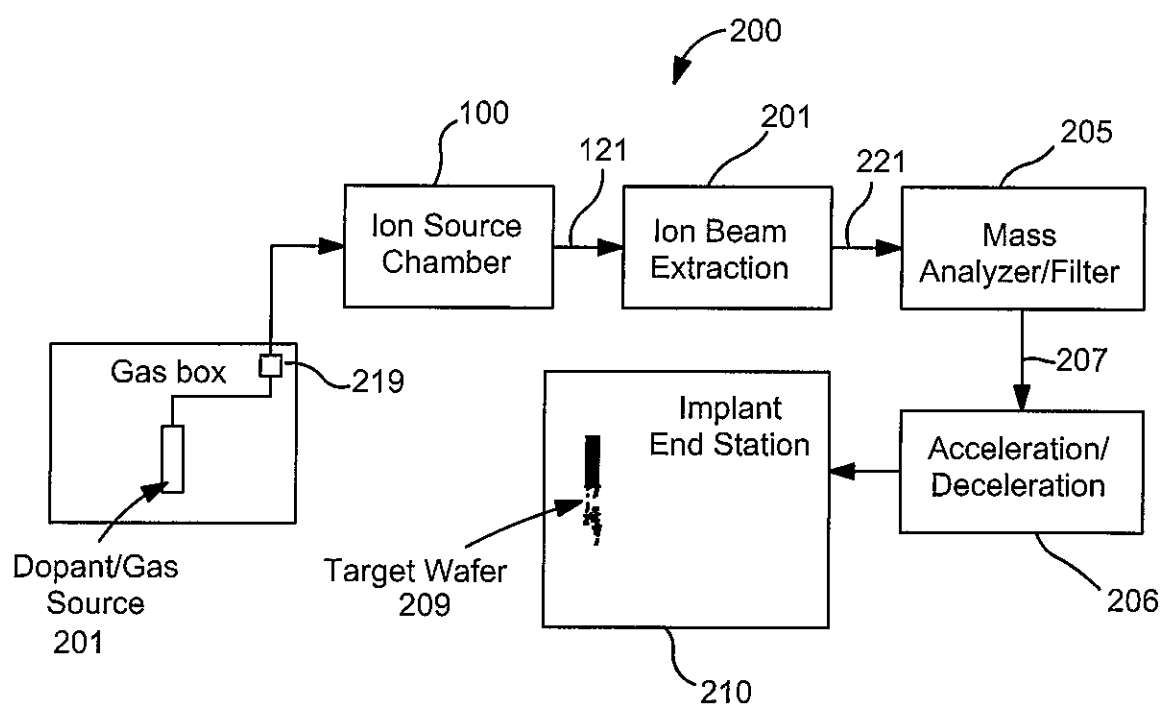


FIG. 2

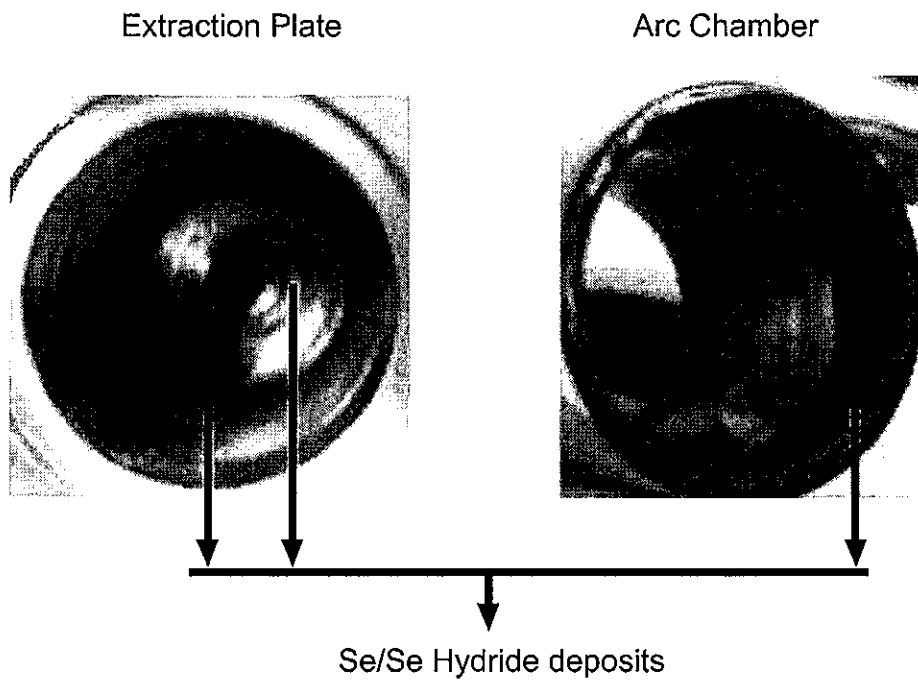
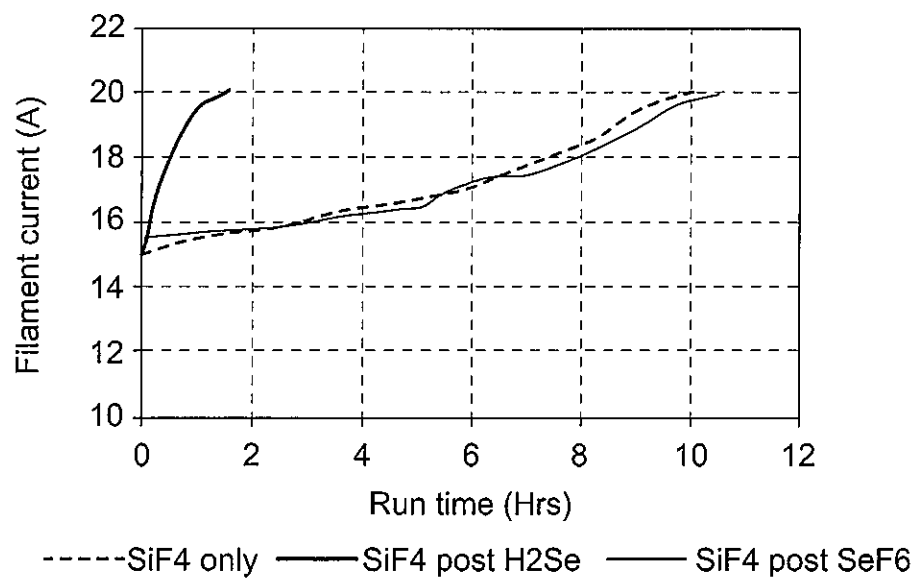


FIG. 3A

FIG. 3B

Deposits during H₂Se Implant



Filament current trend during SiF4 implant

FIG. 4

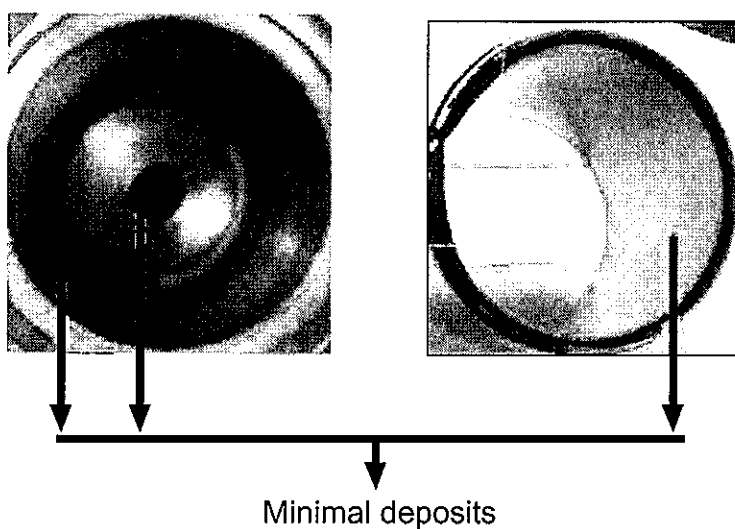


FIG. 5A

FIG. 5B

Deposits during enriched SeF_6 implant